

10/505320

FORM PTO-1449	SERIAL NO. To Be Assigned	CASE NO. 10808/148
LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT (use several sheets if necessary)	FILING DATE 05/05/05 Herewith	GROUP ART UNIT 2827
APPLICANT(S): Franz Hofmann et al.		

REFERENCE DESIGNATION		U.S. PATENT DOCUMENTS			
EXAMINER INITIAL	DOCUMENT NUMBER Number-Kind Code (if known)	DATE	NAME	CLASS/ SUBCLASS	FILING DATE
HH	A1 4,590,589	05/20/1986	Gerzberg		
HH	A2 5,363,329	11/08/1994	Troyan		
HH	A3 5,812,441	09/22/1998	Manning		
HH	A4 5,978,258	11/02/1999	Manning		
HH	A5 2002/0196652	12/26/2002	Mills, JR.		

EXAMINER INITIAL	OTHER ART - NON PATENT LITERATURE DOCUMENTS	
	(Include name of author, title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date page(s), volume-issue number(s), publisher, city and/or country where published.)	
HH	A6	C.P Collier et al, "Electronically Configurable Molecular-Based Logic Gates", Science, Vol. 285, pgs. 391-394, (1999).
HH	A7	C.P. Collier et al, "A [2]Catenane-Based Solid State Electronically Reconfigurable Switch", Science, Vol. 289, pgs. 1172-1175, (2000).
HH	A8	D.I. Gittins et al., "A Nanometre-Scale Electronic Switch Consisting of a Metal Cluster and Redox-Addressable Groups", Nature, Vol. 408, pgs. 67-69, (2000).
HH	A9	G. Wicker et al., "Nonvolatile, High Density, High Performance Phase Change Memory", www.Ovonyx.com, 9 pages, (1999).
HH	A10	A. Beck et al., "Reproducible Switching Effect in Thin Oxide Films for Memory Applications", Applied Physics Letters, Vol. 77, pgs. 139-141, (2000).
HH	A11	H.J. Gao et al., "Reversible, Nanometer-Scale Conductance Transitions in an Organic ...", Physical Review Letters, Vol. 84, No. 8, pgs. 1780-1783, (2000).

EXAMINER	/Huan Hoang/	DATE CONSIDERED	12/24/2006
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609;
 Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.